
PRECISE SELECTIVE DOPING AND METALLIZATION FOR NEXT-GENERATION PERC TECHNOLOGY



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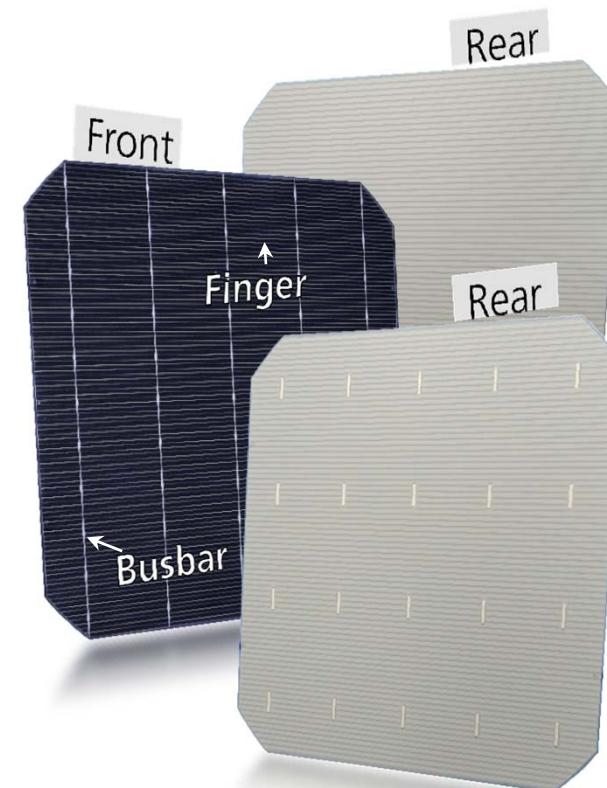
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AGENDA

- Motivation
 - PERC's roadmap according to ISE
 - ITRPV predictions
- Approach
 - PERC base line
 - Precise, congruent patterning
- Application
 - Selective emitter PERC
 - Bifacial cells
- Conclusions



ITRPV: International Technology Roadmap for Photovoltaic

Motivation

PERC's roadmap according to ISE

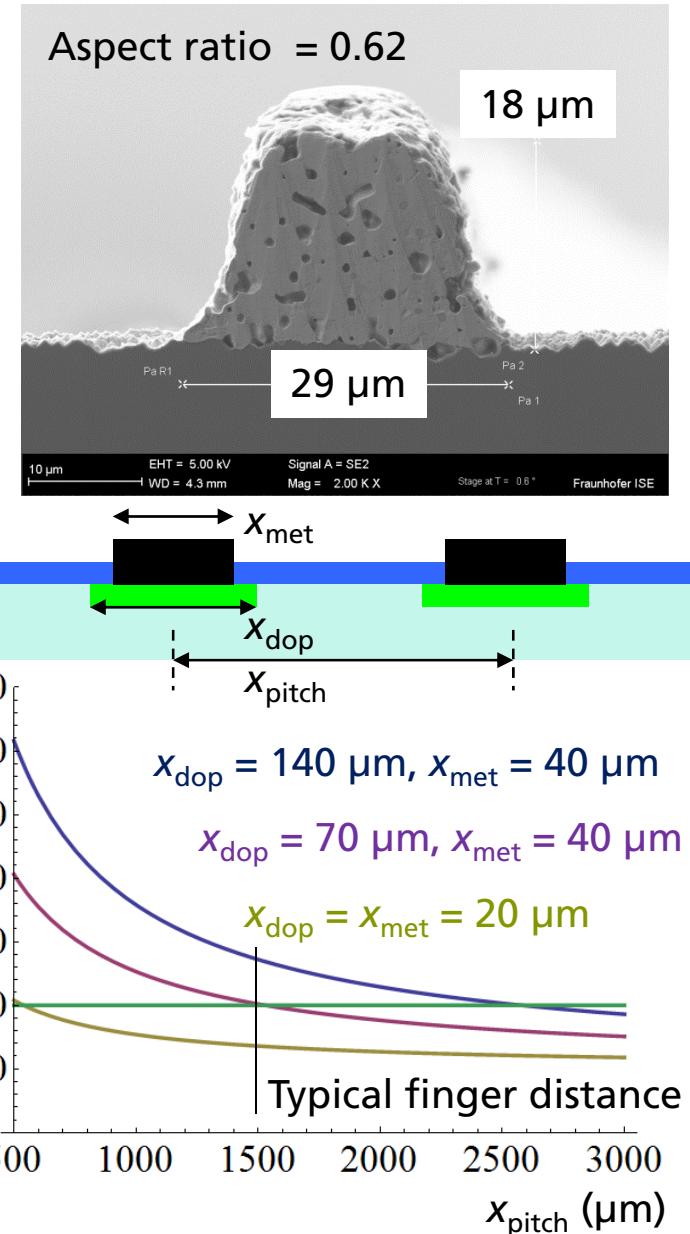
- 7-step program to 240 W/m² *
 - 1: Fine, high aspect ratio front contacts
 - **2: No-overlap selective emitters**
 - 3: Low-cost, high quality material
 - 4: Increased productivity
 - **5: Bifaciality**
 - 6: Bifacial shingled cells with passivated edge
 - 7: Introduction of passivated contacts

Motivation

ITRPV predictions for 2029

- Feature size target
 x_{met} **below 20 µm**
- Effective dark saturation current density target per side
 $J_{0,\text{eff}}$ **below 40 fA/cm²**
- Precision enables ITRPV predictions
- Max. alignment tolerance of $\pm 15 \mu\text{m}$

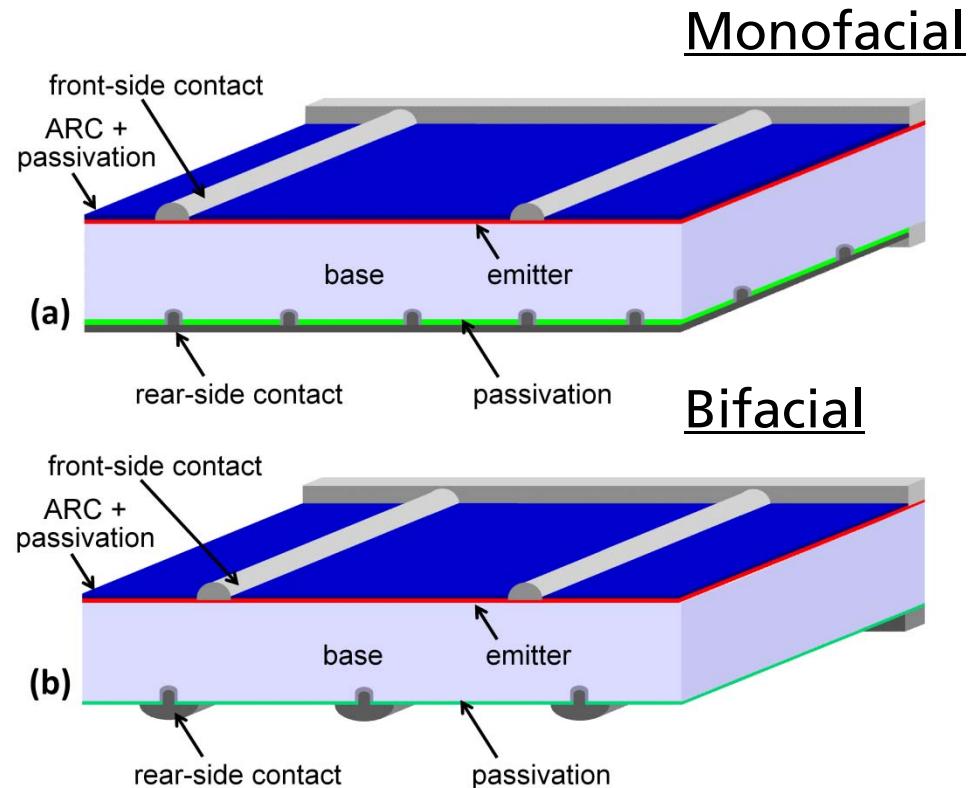
ITRPV, 2018 Results, Tenth Edition, March 2019



Motivation

ITRPV predictions for 2029

- Bifacial cells enable
 - Collection of light from both solar cell sides
 - Additional **yield by 10 - 40% [1-3]**
- Bifacial cells will gain market share
 - 15% in 2019
 - **60% in 2029**
- Even more patterning



[1] L. Podlowski et al., Bifi workshop, 2017;

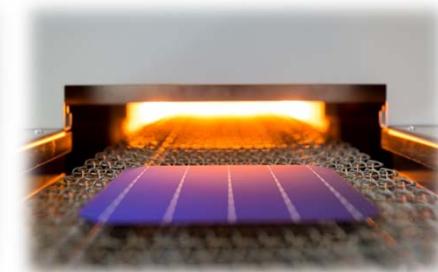
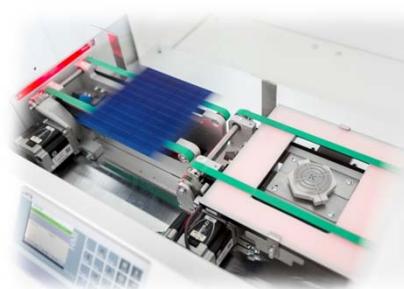
[2] N. Eisenberg, R. Kopecek, V. Fakhfouri et al., PV-tech.org, 2017;

[3] A. Flores et al., Taiyang News, 2017;

Approach

PERC base line process

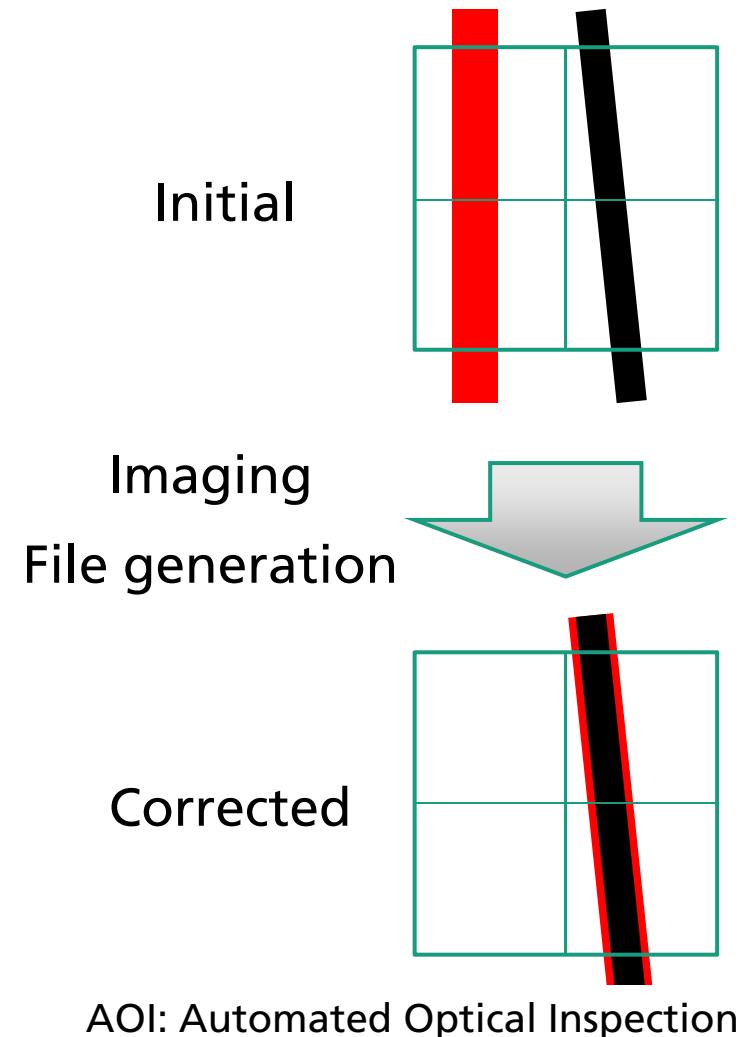
- Industrial PERC solar cells processed in two separate pilot-lines
 - Front-End (no metal)
 - Back-End
- Efficiency of **21.6 %**
- Evaluation of
 - Machines and Components
 - Materials like **solar cell precursors**



Approach

Precise, congruent patterning

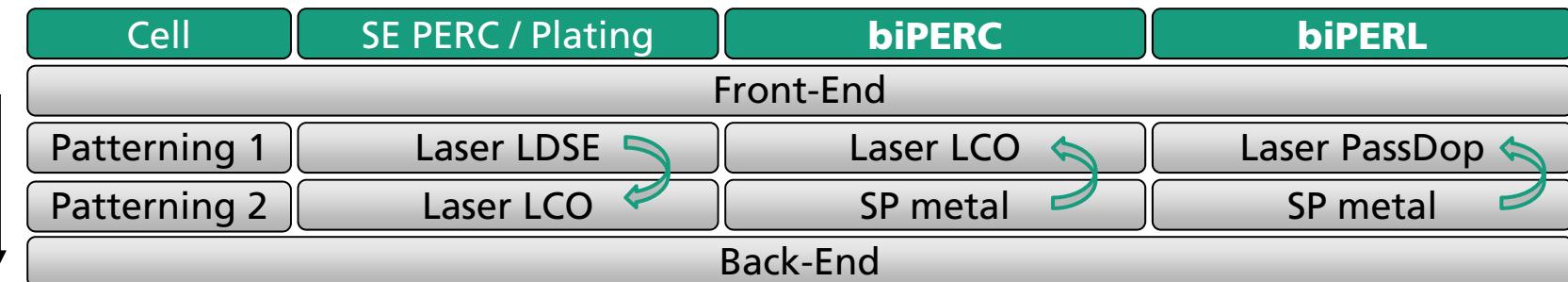
- Digital file generation based on e.g. screen-printed pattern
- Procedure
 - Fabrication of test samples
 - Imaging, $r_{x,y} = 5 \mu\text{m}$
 - Shape determination
 - Offset determination
 - Typ. max. offset $\pm 50 \mu\text{m}$
 - Shape-congruent file generation incl. Offset (algorithm)
 - Vision: AOI meets file generation



Approach

Industrial application

- Patterning process 2 and 1 can be adapted to each other
- Patterning process 1 can be adapted to process 2 and the processes are directly in a row
 - Potential industrial PERC upgrades



- R&D option: SE PERC; inkjet for ink&etch doping and screen printing for metallization;

LDSE: Laser-diffused sel. Emitter; LCO: Laser contact opening; SP: Screen printing;
SE: Selective emitter;

Application I (R&D)

Selective emitter PERC

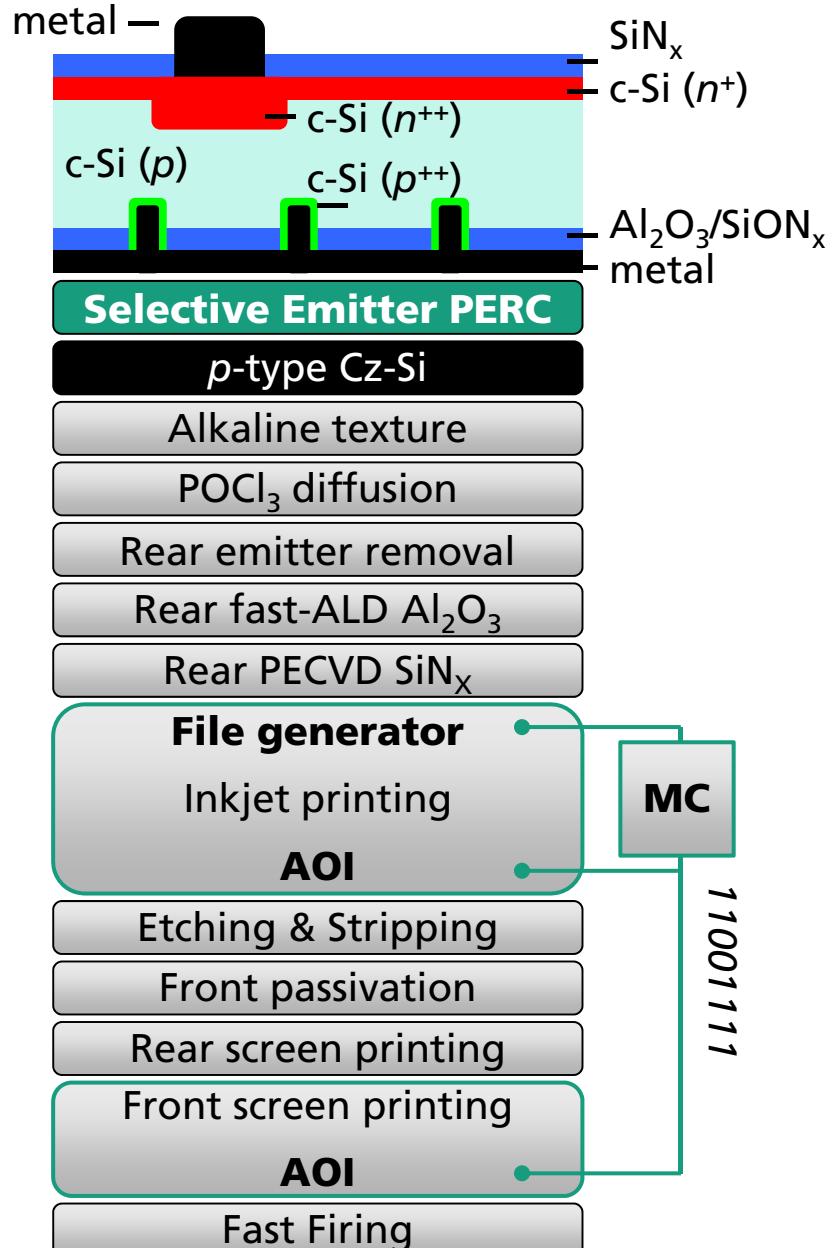
Screen-printed metal on ink&etch doping



Selective Emitter PERC Patterning

- Doping patterning
 - Diffusion
 - Ink&etch of c-Si (n^{++})
- Metal application
 - Screen printing
 - Alternatives at ISE
 - Rotational printing
 - Flexo and Rotational SP
 - Dispensing

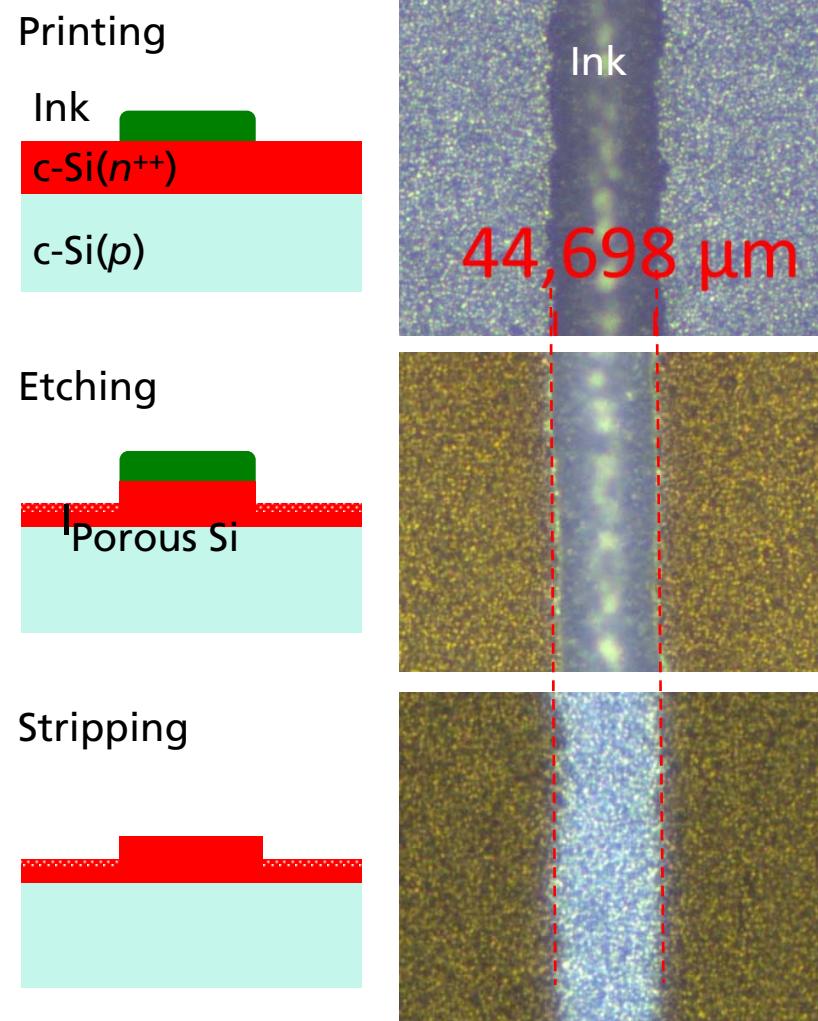
MC: Microcontroller



Selective Emitter PERC

Feature size of c-Si(n^{++})

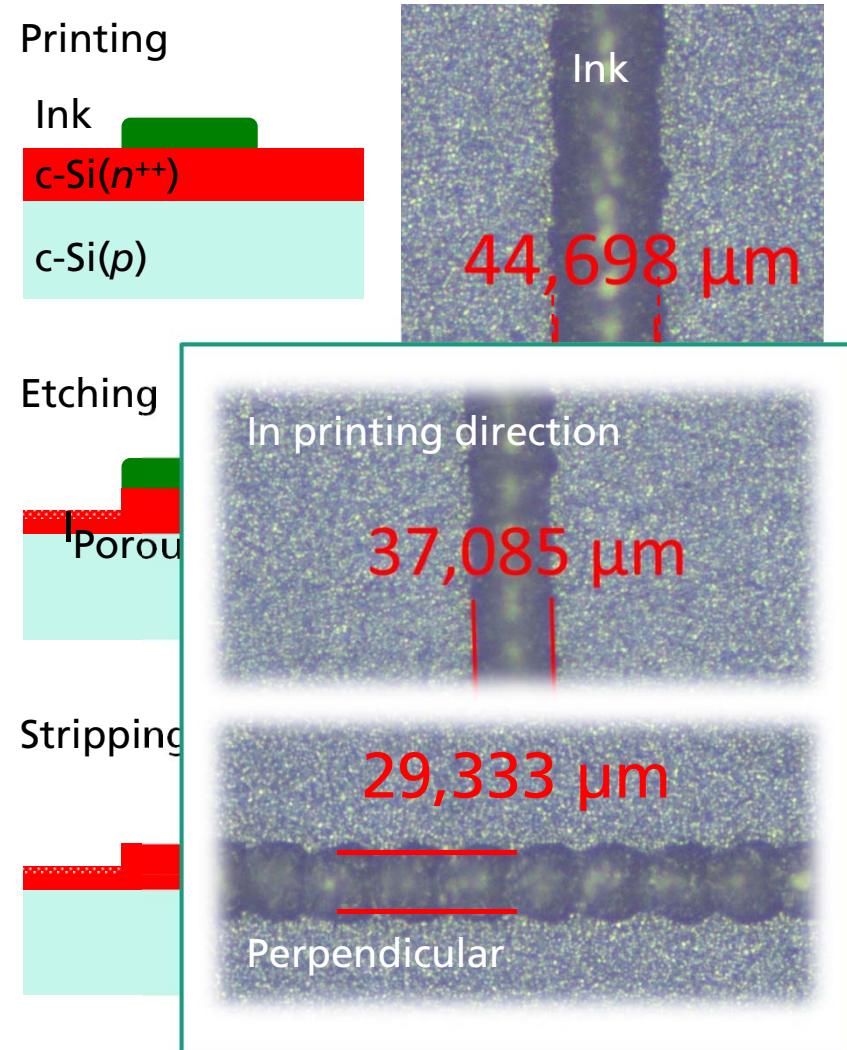
- Technique
 - Inkjet of wax
 - Selective etching of silicon
 - Stripping and cleaning
- No underetching detected
- Feature size of c-Si(n^{++}) equals jetted lines
 - Minimum feature size **below 30 μm**



Selective Emitter PERC

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Selective Emitter PERC

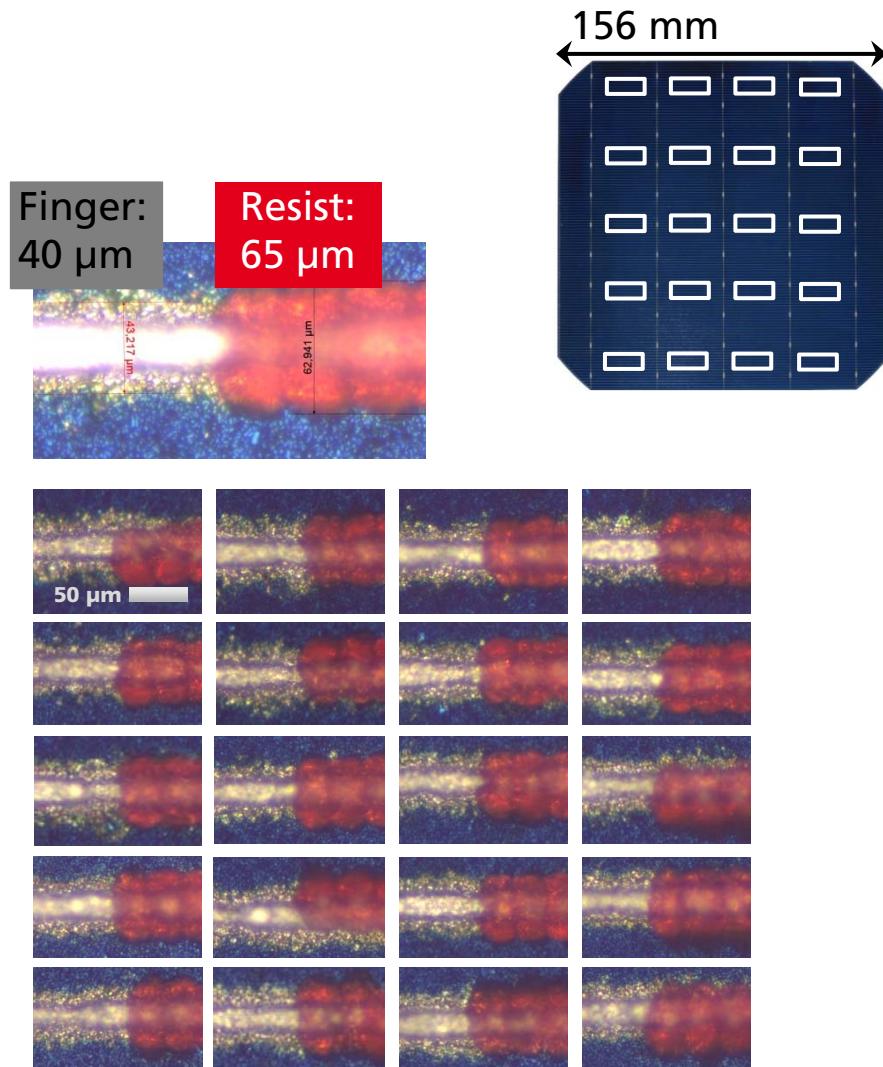
Alignment precision

■ Method

- Screen printing of fingers
- Inkjet printing of **adapted pattern** incl. **interrupted lines** for visualization
- Microscopy of around 1000 positions per wafer

■ Result

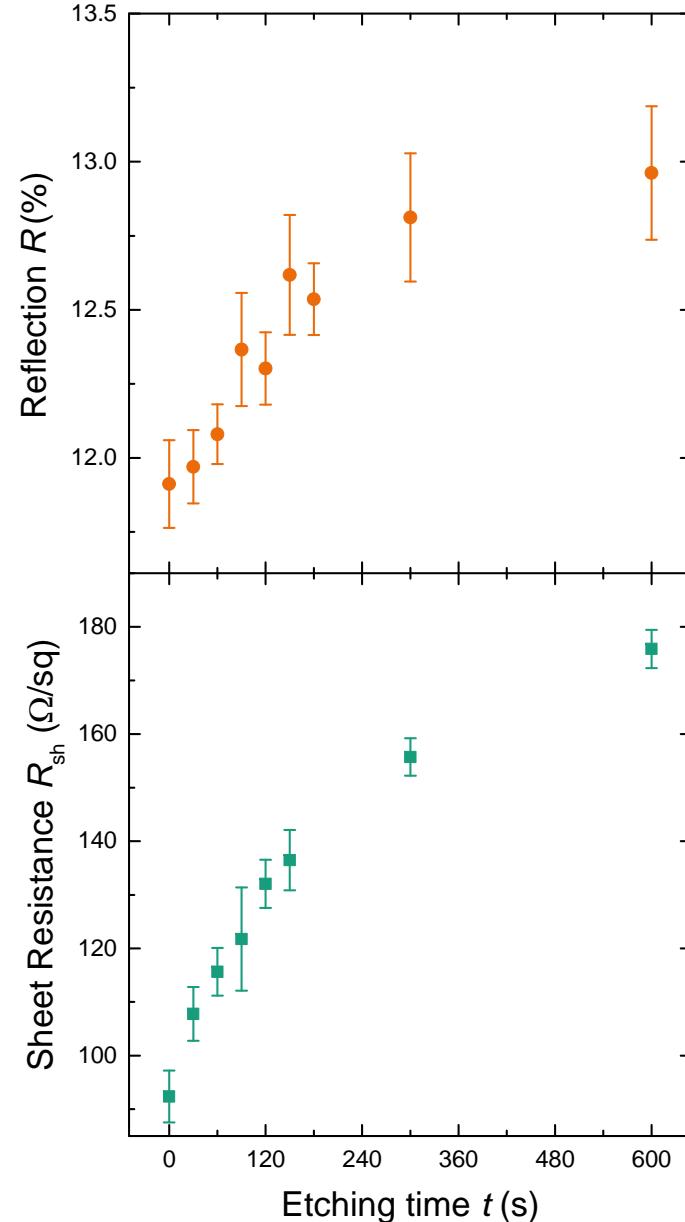
- Alignment accuracy **below $\pm 15 \mu\text{m}$**



Selective Emitter PERC

Reflection and sheet resistance

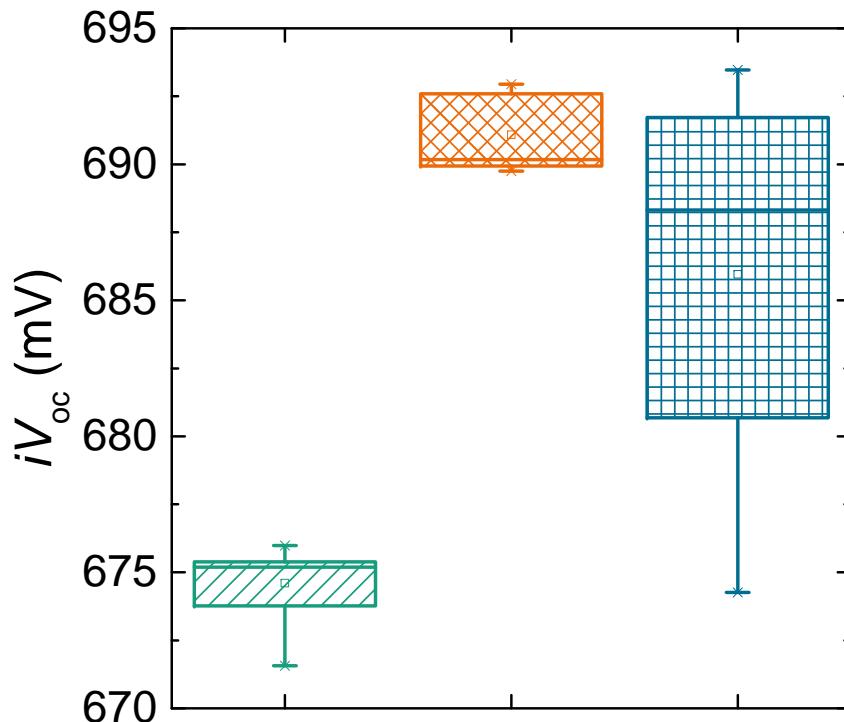
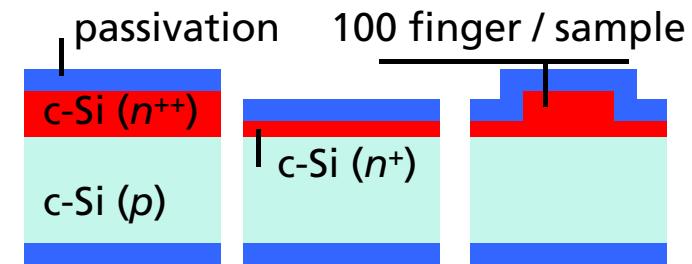
- Sheet resistance R_{sh} adjustable with etching time
- Minor increase in reflection due to rounding of pyramids' tips
- **Trade-off** between resistive and recombination losses at $R_{sh} = 120 \Omega/\text{sq}$



Selective Emitter PERC

Recombination

- Evaluation of recombination by QSSPC and unsymmetrical sampling
- Silicon etching improves implied open circuit voltage iV_{oc} by around **20 mV**
- Selective silicon etching leads to a decrease in homogeneity
 - Interaction between ink and etching media assumed



QSSPC: Quasy steady state photo conductance

Application II (Industry)

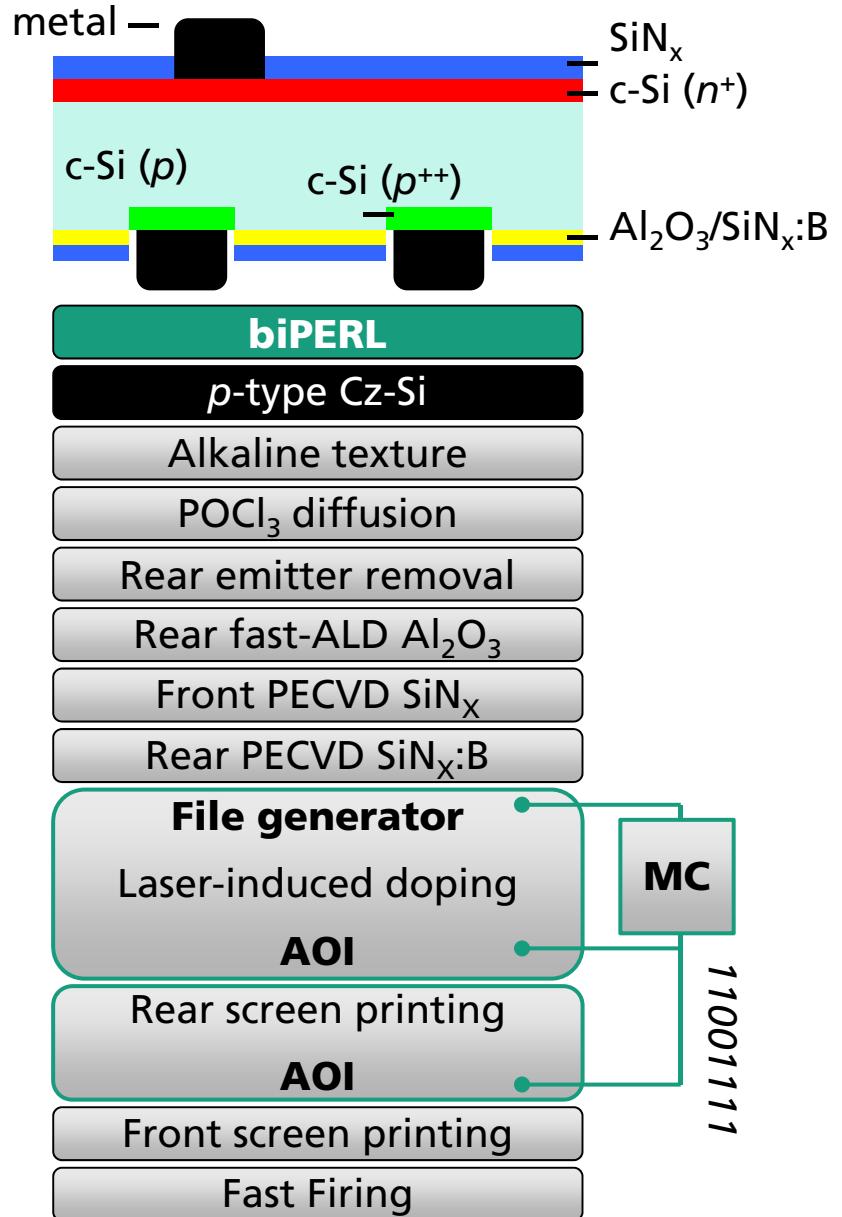
Bifacial cells

Screen-printed metal on laser-induced doping (pPassDop) and Laser Contact Opening (LCO)



Bifacial PERL *Patterning*

- Compatible with existing cell fabs
- Laser processing and screen printing **in a row**
- Compatible with hazardous failure of screen printers
- Doping patterning
 - **pPassDop**
 - Deposition of $\text{Al}_2\text{O}_3/\text{SiN}_x:\text{B}$
 - Laser-induced Al/B doping



Bifacial PERL

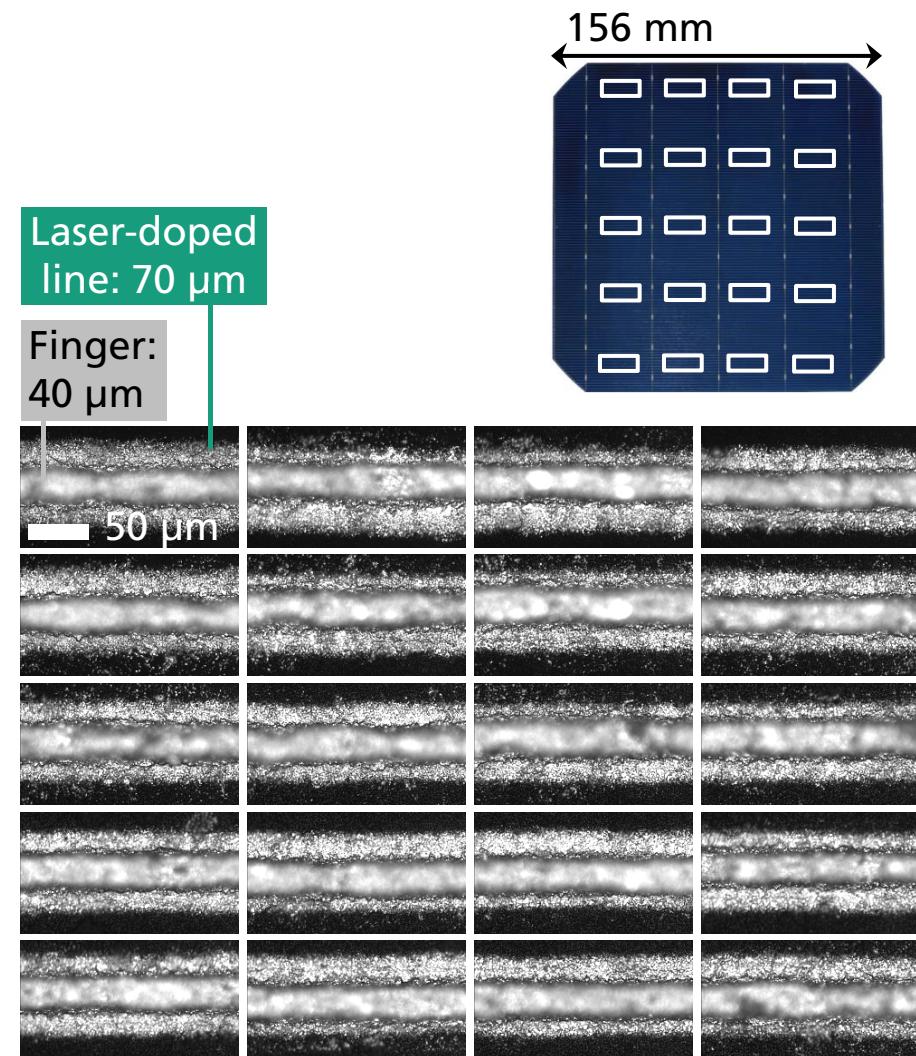
Alignment precision

■ Method

- Laser writing of **adapted pattern**
- Screen printing of fingers
- Microscopy of around 1000 positions per wafer

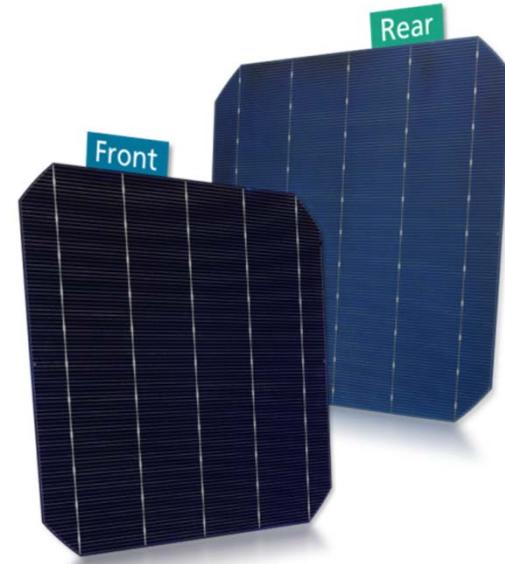
■ Result

- Alignment accuracy **below $\pm 15 \mu\text{m}$**



E. Lohmüller et al., WCPEC, 2018

Solar cell results



Type	Prec.	V_{oc} (mV)	J_{sc} (mA/cm ²)	FF (%)	η_{front} (%)	η_{rear} (%)	β (%)	p_{out}^* (mW/cm ²)
monoPERC	ISE	667	40.2	80.7	21.6			21.6
biPERL [1]	ISE	651	39.2	79.9	20.4	18.0	88	22.2

* p_{out} for $G_{front} = 100 \text{ mW/cm}^2$ (STC) and $G_{rear} = 10 \text{ mW/cm}^2$;

Conversion efficiencies measured on a black chuck;

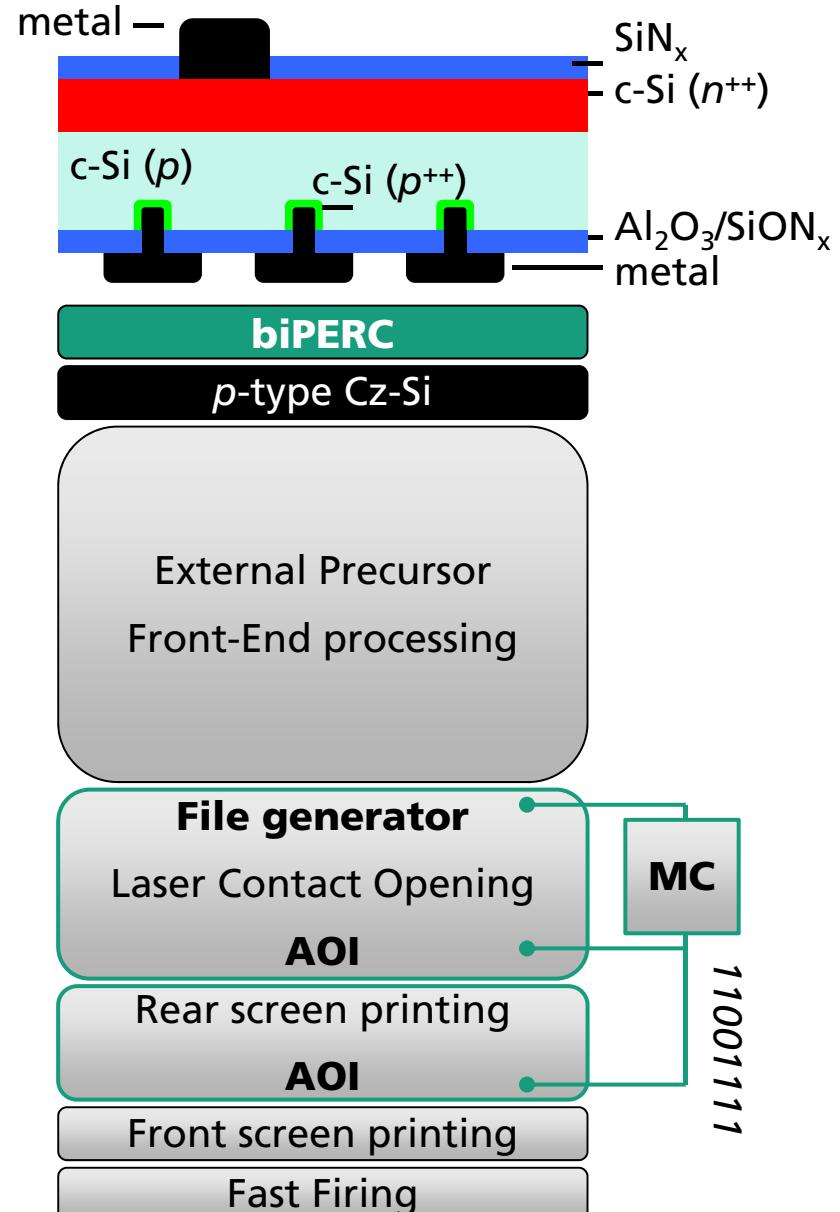
[1] E. Lohmüller et al., WCPEC, 2018

Bifacial PERC *Patterning*

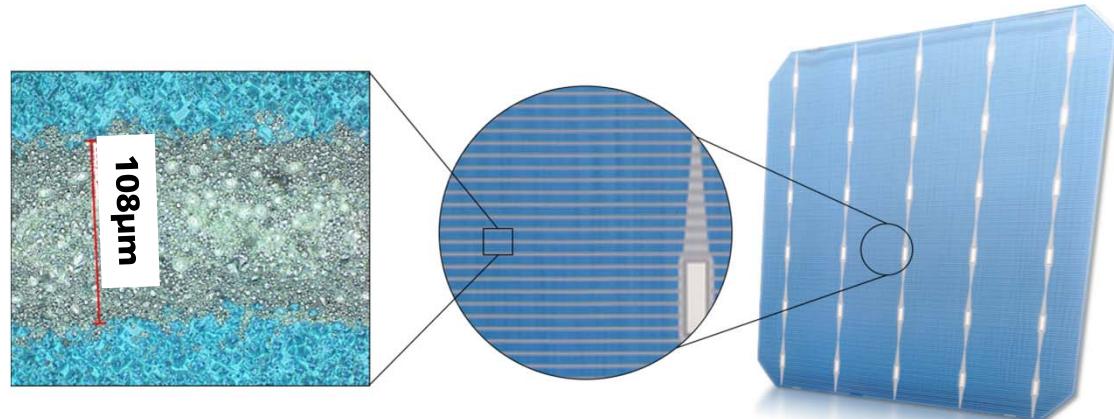
- LCO patterning
- Laser processing

- Metal application
 - Screen printing
 - Al Paste (not firing-through)

- Contact formation
 - Fast Firing
 - Al-Si alloying



Solar cell results



- Generally: method works stable on e.g. 100 μm Al on 30 μm LCO

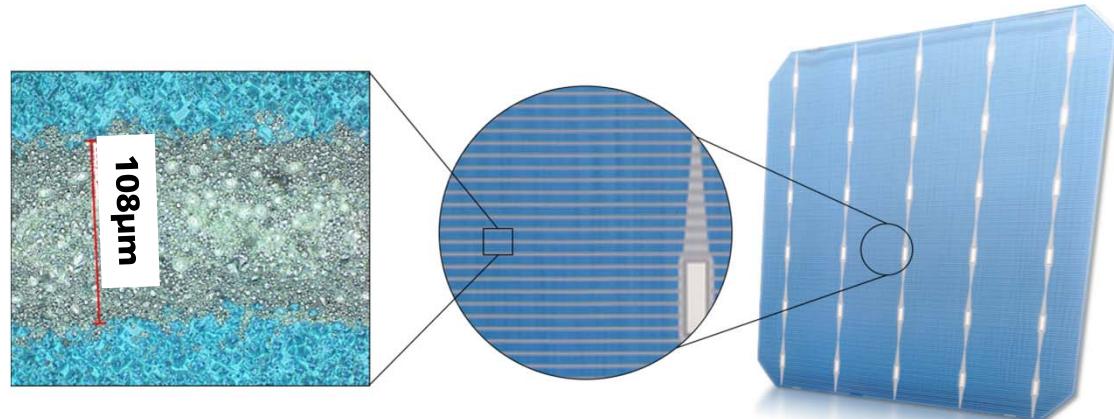
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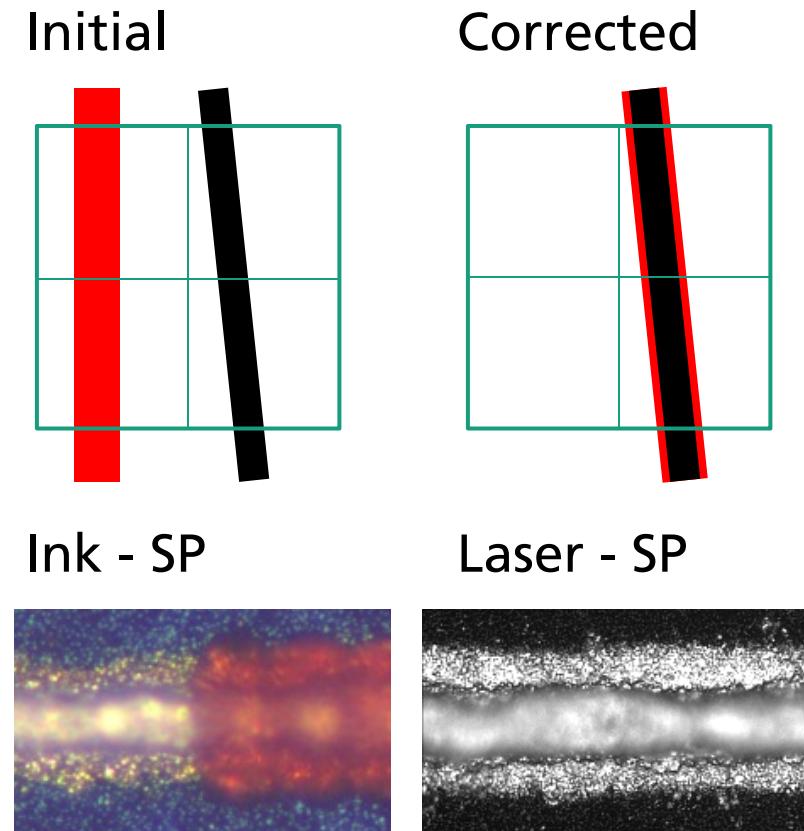
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Conclusion

- Digital method established for precise, shape-congruent patterning
 - Scalable with AOI
- High alignment accuracy of $\pm 15 \mu\text{m}$ between different patterning methods

- Successful process integration
 - biPERL (*p*-type)
 - biPERC (*p*-type)



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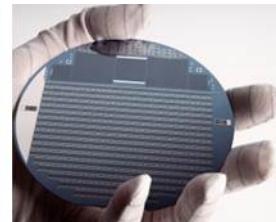
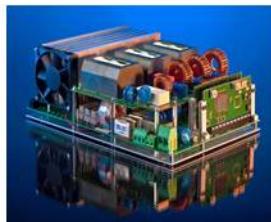


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on the basis of a decision
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